



School on Synchrotron and FEL Based Methods and their Multi-Disciplinary Applications

19 - 30 March 2012

Additional information lecture 1

Charles S. Fadley Univ. of California Davis & LBNL USA

Characterization of Surfaces, Interfaces, and Complex Materials with Core and Valence Photoemission

Chuck Fadley Dept. of Physics, UC Davis and Materials Sciences Division Lawrence Berkeley National Laboratory Supported by: U.S. Dept. of Energy Humboldt Foundation & Helmholtz Association Jülich Research Center

School on Synchrotron Radiation and FEL Based Methods and their Multi-Disciplinary Applications March 26, 2012

Photoelectron spectroscopy = Photoemission: The Basic Elements

Friday, 23 March 2012	
Room: Adriatico Guest House Giambiagi Lecture Hall	
09:00 Surfaces, Interfaces & Photoelectron Spectroscopy 01h30' 10:30	A. Goldoni Sincrotrone Trieste
10:30 BREAK 30' 11:00	
11:00 ARPES 01h30' 12:30	A. Goldoni Sincrotrone Trieste
12:30 14:00	
14:00 Inelastic X-ray Scattering: principles and application 01h30' 15:30	F. Bencivenga Sincrotrone Trieste
15:30 BREAK 30' 16:00	
16:00 Electronic structure and atomistic computations for the interpretation of synchrotron experiments 01h00+ 17:00	N. Binggeli ICTP

Monday, 26 March 2012	
Room: Adriatico Guest House Giambiagi Lecture Hall	
09:00 Photoelectron Diffraction and holography 01h30'	Charles S. Fadley
10:30	Univ. of California Davis & LBNL (USA)
10:30 BREAK 30' 11:00	
11:00	Charles S. Fadley
12:30 Core Level shifts, splitting and dichroism 01h30	Univ. of California Davis & LBNL (USA)
12:30 14:00	
14:00 Low density matter: spectroscopy and scattering 01h30'	M. Simon
15:30	University Pierre et Marie Curie, France
15:30 BREAK 30' 16:00	
16:00 Low_density matter: ultrafast dynamics 01h00*	M. Simon
17:00	University Pierre et Marie Curie, France
17:00	P. Decleva
18:30	University of Trieste

Link to archive of longer set of lectures in 2010, plus guides to use of SESSA and EDAC simulation programs:

http://www.yousendit.com/download/M3Btb2VDeFU3N0RFdzhUQw

General references on various aspects of photoelectron spectroscopy, diffraction, holography (available at School website and/or Fadley group website: <u>http://www.physics.ucdavis.edu/fadleygroup/</u> :

Paper [1] "Basic Concepts of X-ray Photoelectron Spectroscopy", C.S.F, in <u>Electron Spectroscopy</u>, <u>Theory, Techniques, and Applications</u>, Brundle and Baker, Eds. (Pergamon Press, 1978) Vol. II, Ch. 1.

Paper [2] "Atomic-Level Characterization of Materials with Core- and Valence-Level Photoemission: Basic Phenomena and Future Directions", C.S. Fadley, Surf. Interface Anal. 2008, 40, 1579–1605.

Paper [3] "X-ray photoelectron spectroscopy: Progress and perspectives" C.S. Fadley, Journal of Electron Spectroscopy and Related Phenomena 178–179 (2010) 2–32

Key Reference: "X-ray Data Booklet", Center for X-Ray Optics and the Advanced Light Source, LBNL, January, 2001, available online at: http://xdb.lbl.gov/

Additional very useful websites:

X-ray optical calculations: reflectivities, penetration depths for a variety of mirror/surface geometries http://www-cxro.lbl.gov/optical_constants/

General properties of the elements and their compounds: <u>http://www.webelements.com</u>

Simulation of photoelectron and Auger spectra with program SESSA: See "SESSA: A Brief Manual", with download instructions, etc.

Simulation of x-ray photoelectron diffraction (XPD) with program EDAC: See guide example calculation for CO on Fe.

X-RAY DATA BOOKLET Center for X-ray Optics and Advanced Light Source Lawrence Berkeley National Laboratory

http://xdb.lbl.gov/

Introduction

- X-Ray Properties of Elements
- Electron Binding Energies
- **3** X-Ray Energy Emission Energies
- Fluorescence Yields for K and L Shells
- **Organization Principal Auger Electron Energies**
- Subshell Photoionization Cross-Sections
- Mass Absorption Coefficients
- Atomic Scattering Factors
- Energy Levels of Few Electron Ions
- Periodic Table of X-Ray Properties
- Synchrotron Radiation
- Characteristics of Synchrotron Radiation
- History of X-rays and Synchrotron Radiation
- Synchrotron Facilities
- Scattering Processes
- Scattering of X-rays from Electrons and Atoms
- <u>Low-Energy Electron Ranges in Matter</u>
- Optics and Detectors
- Orystal and Multilayer Elements
- Specular Reflectivities for Grazing-Incidence Mirrors
- Gratings and Monochromators
- Zone Plates
- <u>X-Ray Detectors</u>
- Miscellaneous
- Physical Constants
- Physical Properties of the Elements
- <u>Electromagnetic Relations</u>
- a Radioactivity and Radiation Protection
- <u>Useful Formulas</u>

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Center for X-Ray Optics and Advanced Light Source

X-RAY DATA BOOKLET

Alber! Thompson Ingoil David Attwood Piero Eric Gußikson Arthu Malcoim Howells James Kwang-Je Kim James Janos Kirz Doug Jeffrey Kortnight Gwyn Herman Winick

Ingolf Lindau Fiero Pianetta Arthur Robinson James Scofield James Underwood Douglas Vaughan Gwyn Williams n Winick

January 2001

Lawrence Berknieg National Lawrency Conversity of Cathornia Berkeleg, CA 94720

This work was accepted as set, by the U.S. Deportment of foreign order Contract the DF-AC20-PCF/00/re



H1	Periodic Table, with the Outer Electron Configurations of Neutral															He ²								
1s	Periodic Table, with the Outer Electron Configurations of Neutral Atoms in Their Ground States Be ⁴ The notation used to describe the electronic configuration of atoms B ⁵ C ⁶ N ⁷ O ⁸ F ⁹															152								
Li ³	Be ⁴	The	nota	ation	used	l to d	desc	ribe t	he e	lectro	nic co	onfi	gura	tior	n of	atom	s	B ⁵	C ₆	N ⁷		O ⁸	F ⁹	Ne ¹⁰
28	2s ²	and The mom	letters s, p, d, signify electrons having orbital angular entum 0, 1, 2, in units \hbar ; the number to the left of the r denotes the principal quantum number of one orbit, and the														⁵ 2s ² 2p							
Na ¹¹	Mg ¹²	lette supe	r de rscr	enotes the principal quantum number of one orbit, and the right denotes the number of electrons in the orbit. AI^{13} Si^{14} P^{15} S^{16} CI^{17} Ar^{13}														Ar ¹⁸						
38	3s ²			$3s^{2}3p \ 3s^{2}3p^{2} \ 3s^{2}3p^{3} \ 3s^{2}3p^{4} \ 3s^{2}3p^{5} \ 3s^{2}$														5 3s ² 3p						
K ¹⁹	Ca ²⁰	Sc ²¹	Ti	22	V^{23}	C	r ²⁴	Mn ²⁵	Fe	e ²⁶	Co ²⁷	N	j ²⁸	Cu	29	Zn ³	0 -	Ga ³¹	Ge ³²	As ³	3	Se ³⁴	Br ³⁵	Kr ³⁶
4 s	4s ²	$\frac{3d}{4s^2}$	30 48	d^2 s^2	$\frac{3d^3}{4s^2}$	30 48	l ⁵	${3d^{5}\over 4s^2}$	30 4s	1 ⁶	$3d^7$ $4s^2$	30 48	d^{8}	3d 4s	10	$\frac{3d^{1}}{4s^{2}}$	0	ls²4p	$4s^24p^2$	4s ² 4	p^3	$4s^24p^4$	4s ² 4p	⁵ 4s ² 4p
Rb ³⁷	Sr ³⁸	Y ³⁹	Zı	-40	Nb ⁴¹	M	0 ⁴²	TC ⁴³	R	u ⁴⁴	Rh ⁴⁵	P	d ⁴⁶	Ag	47	Cd ⁴	8	n ⁴⁹	Sn ⁵⁰	Sb ⁵	1	Te ⁵²	1 53	Xe ⁵⁴
5s	5s ²	$\frac{4d}{5s^2}$	40 5s	$d^{2}_{,2}$	4d ⁴ 5s	.40 5s	ł ⁵	$4d^{6}$ 58	4a 5s		$4d^{s}$ 5s	40	d 10	4d 5s	10	$\frac{4d^{1}}{5s^{2}}$	0	$5s^25p$	$5s^25p^2$	5s ² 5	$5p^3$	$5s^25p^4$	5s ² 5p	⁵ 5s ² 5p
Cs55	Ba ⁵⁶	La ⁵⁷	H	72	Ta ⁷³	W	74	Re ⁷⁵	0	S ⁷⁶	lr ⁷⁷	Pt	78	Au	79	Hg ⁸	0 7	1 ⁸¹	Pb ⁸²	Bi ⁸³	1	P0 ⁸⁴	At ⁸⁵	Rn ⁸⁶
<u>6</u> s	6s ²	$5d$ $6s^2$	4 <i>f</i> 5 <i>c</i> 6s	l^2_2	5d ³ 6s ²	5a 6s	l ⁴ 2	$5d^{5}$ $6s^{2}$	50 6s	1 ⁶	5d ⁹	50 6s	19 :	5d 6s	10	$5d^{10}$ $6s^{2}$. 6	s²6p	$6s^26p^2$	6s ² 6	p^3	$6s^26p^4$	$6s^26p^3$	6s ² 6p
Fr ⁸⁷	Ra ⁸⁸	Ac ⁸⁹		0.5					61					_				-				-		
7s	7s ²	$\frac{6d}{7s^2}$		$4f^2$	° Р 4j	r ³⁹	NC 4f	⁴ 4	m ⁶¹ f ⁵	Sm ⁶	² Eu 4 <i>f</i>	1 ⁶³ 7	G 4f 5d	64 7	Tb 4 <i>f</i> [*] 5 <i>d</i>	65	Dy ⁶⁶ 4f ¹⁰	H 4j	0 ⁶⁷ Er ¹¹ 4 <i>f</i>	•68 `12	Tm^{4}	69 YE 3 4f	⁷⁰ L ¹⁴ 4 5	$ u^{71} f^{14} d $
			Y	05- Th9	6	9 ²	05-	0.	S ²	6s ²	65	05	6s ²	0.0	6s ²		6s ²	6s	² 6s	2	6s ²	6s ²	e 6	s ²
				$-6d^2$	5j 6d	f ²	5f ³ 6d	5 5	p ³³ f ⁵	5f ⁶	5f	n ⁹⁵ 7	Cn 5f 6d	n ⁹⁶ 7	Bk	97	Cf ⁹⁸	E	5 ⁹⁹ Fn	n ¹⁰⁰	Md	NC) ¹⁰²	r ¹⁰³
			l	$7s^2$	7:	8 ²	$7s^2$	7:	s ²	$7s^2$	7s ²	2	$7s^2$											

Н ¹ 4К hcp 3.75 6.12		The o the s see V there	data tateo Wycl	give l ten coff,	Tab en are npera Vol.	e at roo ature i 1, Ch	Crys om t n de ap.	empera g K. F 2. Stru	ature or fu	res of the for the rther do es label	he ele mos escrip led co	eme at co otion omp	ents ommo ns of olex a	on fo the are c	rm, c elem lescri	or at ents ibed								He ⁴ 2K hcp 3.57 5.83
Li 78K bcc 3.491	Be hcp 2.27 3.59														(B	ıb.	C diamond 3.567	N 201 cubic 5.66 (N ₂)	com (O ₂	plex)	F	Ne 4К fcc 4.46
Na 5K bcc 4.225	Mg hcp 3.21 5.21						a lat c lat	Crystal ttice pa ttice pa	struc rame rame	cture. eter, in A eter, in A						\rightarrow \rightarrow	AI fcc 4.0	5	Si diamond 5.430	P complex	S com	plex	CI complex (CI ₂)	Ar 4K fcc 5.31
К 5К bcc 5.225	Ca fcc 5.58	Sc hcp 3.31 5.27	Ti hc 2.9 4.6	p 95 58	V bcc 3.03	Cr bc 2.8	c 38	Mn cubic complex	Fe bco 2.8	c hc 37 2.9 4.0	p 51 07	Ni fcc 3.5	2	Cu fcc 3.61	Z ho 2. 4.	n cp .66 .95	Ga	plex	Ge diamond 5.658	As rhomb.	Se hex. chai	ns	Br complex (Br ₂)	Кг 4К fcc 5.64
Rb 5K bcc 5.585	Sr fcc 6.08	Y hcp 3.65 5.73	Zr hcj 3.2 5.1) 23 5	Nb bcc 3.30	M (bcc 3.1) 5	Tc hcp 2.74 4.40	Ru hcp 2.7 4.2	Rh p fcc '1 3.8 '8	n : 30	Pd fcc 3.89	1 9 4	Ag fcc 4.09	C hc 2. 5.	d p 98 62	In tetr 3.25 4.95	 5 . 5	Sn (α) diamond 6.49	Sb rhomb.	Te hex. chain	ns	l cómplex (l ₂)	Xe 4K fcc 6.13
Сs 5К bcc 6.045	Ba bcc 5.02	La hex. 3.77 ABAC	Hf hcj 3.1 5.0	9 95	Ta bcc 3.30	W bco 3.1	с .6	Re hcp 2.76 4.46	Os hcp 2.7 4.3	lr 5 fcc 74 3.8 82	: 34	Pt fcc 3.92	2	Au fcc 4.08	H	g omb.	TI hcp 3.40 5.52	6 4 2	Pb fcc 4.95	Bi rhomb.	Po sc 3.3	4	At —	Rn —
Fr —	Ra —	Ac fcc 5.31		Ce fcc 5.1	6	Pr hex. 3.67 ABAC	Nd hex 3.6	6 —	m -	Sm complex	Eu bcc 4.58	8	Gd hcp 3.63 5.78	-	Tb hcp 3.60 5.70	Dy hc; 3.5 5.6	o 59 55	Ho hcp 3.58 5.62	Er hcj 3.5 5.5	p h 56 3 59 5	m cp .54 .56	Yb fcc 5.4	E hu	J 20 50 55
				Th fcc 5.0	8	Pa tetr. 3.92 3.24	U com	Diex cor	P nplex	Pu complex	Am hex. 3.64 ABA	4 AC	Cm		Bk —	Cf		Es —	Fn 	n N	/Id 	No —		r

		ipere	1	3.6 Th	5 3 P	63 a	3.66 U	N	p	3.5 Pu	9 3. A i	96 m	3.5 Cm	8 1	3.52 Bk	2 3 C	.51 f	3.49 Es	3.4 Fn	17 n	3.54 Md	3. N	88 3 o	3.43 _r	
Fr 	Ra —	Ac 10.07 2.66 3.76		Ce 6.7 2.9	P 7 6 1 2	r 78 92	Nd 7.00 2.93	Pi	m	Sm 7.5 3.0	E 4 5. 3 2.	J 25 04	Gd 7.8 3.0	9	Tb 8.27 3.22	2 3	y .53 .17	Ho 8.80 3.22	Er 9.0 3.2	04	Tm 9.32 3.32	Y 6. 3.	b 97 02 3	-u 9.84 3.39	
1.997 0.905 5.235	3.59 1.60 4.35	6.17 2.70 3.73	13 4.5 3.1	.20 52 .3	16.66 5.55 2.86	19 6.3 2.7	.25 80 74	21.03 6.80 2.74	22 7.1 2.6	.58 14 58	22.55 7.06 2.71	21. 6.6 2.7	.47 52 77	19.2 5.90 2.88	28	14.26 4.26 3.01	11 3.9 3.4	.87 1. 50 3. 46 3.	1.34 30 50	9.80 2.82 3.07) 9 2 2 7 3	.31 .67 .34			
Rb 5к 1.629 1.148 4.837 Сs 5к	Sr 2.58 1.78 4.30 Ba	Y 4.48 3.02 3.55 La	Zr 6.5 4.2 3.1 Hf	51 29 .7	Nb 8.58 5.56 2.86 Ta	Ma 10 6.4 2.7 W	22 22 22 22	Tc 11.50 7.04 2.71 Re	Ru 12 7.3 2.6 Os	.36 36 55	Rh 12.42 7.26 2.69 Ir	Pd 12. 6.8 2.7 Pt	.00 60 75	Ag 10.5 5.85 2.89 Au	i0	Cd 8.65 4.64 2.98 Hg 22	In 7.2 3.8 3.2 7 TI	29 5. 33 2. 25 2. P	n 76 91 81 b	Sb 6.69 3.31 2.91 Bi	7 6 2 2 2 P	e .25 .94 .86	 4.95 2.36 3.54 At		Xе 4к 3.78 1.64 4.34 Rn
К 5к 0.910 1.402 4.525	Ca 1.53 2.30 3.95	Sc 2.99 4.27 3.25	Ti 4.5 5.6 2.8	51 56 39	V 6.09 7.22 2.62	Cr 7.1 8.3 2.5	.9 33 50	Mn 7.47 8.18 2.24	Fe 7.8 8.5 2.4	37 50 18	Co 8.9 8.97 2.50	Ni 8.9 9.1 2.4	01 4 9	Cu 8.93 8.45 2.56		Zn 7.13 6.55 2.66	Ga 5.9 5.1 2.4	G 91 5. 10 4. 14 2.	e 32 42 45	As 5.77 4.65 3.16	S 4 5 3 5 2	.81 .67 .32	Br 12 4.05 2.36	ЗК	Кг 4к 3.09 2.17 4.00
Na 5к 1.013 2.652 3.659	Mg 1.74 4.30 3.20	<			— — C — Ne	Der oncen arest-	nsity i tratic neigh	n g cr n in 1 bor di	n ⁻³ (0 ²² c stanc	10 ³ k m ⁻³ æ, in	g m ⁻³) (10 ²⁸ m Å (10 ⁻	1 ⁻³) ¹⁰ m)				\rightarrow	Al 2.7 6.0 2.8	70 2. 02 5. 36 2.	i 33 00 35	Ρ	S		Cl 93 2.03 2.02	BK I	Аг 4к 1.77 2.66 3.76
і 78К 0.542 1.700 3.023	Be 1.82 12.1 2.22	Ato = r _n = 0	от мт .5	ic I n-r	radi n dis	us st.	~	Av de	era nsi	age ity	<mark>e sur</mark> = ρ _s	fac ≈ (e Pv	2/3			B 2.4 13	C 17 3. .0 17 1.	516 7.6 54	N 24	ok C		F 1.44		Ne 4К 1.51 4.36 3.16
і 4К 0.088		The d stated	ata a ten	ure g nper	Table iven at ature	atmo in de	Dens osphe g K.	ity and ric pro (Crys	d ato essur tal m	omic re an nodifi	concer d room ications	tem s as f	ion pera for T	ture, `able	or a 3.)	at the								(1	Не 2К 0.205 at 37 atm

Li	Ве]	J	[able	e 1 D	ebye	tem	nperatu	ire a	nd t	herma	l con	duct	tivity ^a			В	С		N	0		F	Ne
344 0.85	1440 2.00																0.27	223 1.2	0 9	2 2				75
Na	Mg	2-5-18															AI	Si		Р	s		CI	Ar
158 1.41	400 1.56			Т	Lov Therma	v ten al con	npe	rature ctivity	limi at 3	t of 00 k	θ , in K K, in W	Kelvin / cm ⁻	n -1K	-1			428 2.37	645 1.4	8					92
к	Ca	Sc	Ті		v	Cr	ELS .	Mn	Fe		Co	Ni		Cu	Zn	ority	Ga	Ge		As	Se		Br	Kr
91 1.02	230	360. 0.16	42	20 22	380 0.31	63 0.	0 94	410 0.08	47	0 80	445 1.00	450 0.9))1	343 4.01	32 1.	7 16	320 0.41	374 0.6	0	282 0.50	90 0.	02		72
Rb	Sr	Y	Zı		Nb	M	D	Тс	Ru	1	Rh	Pd		Ag	Co	1	In	Sn	w	Sb	Te	-	I	Xe
56 0.58	147	280 0.17	29 0.)1 23	275 0.54	45	0 38	0.51	60 1.	0 17	480 1.50	274 0.7	1 72	225 4.29	20 0.	9 97	108 0.82	200 0.6	7	211 0.24	15 0.	.3 02		64
Cs	Ва	La β	н	f	Та	w		Re	Os		lr	Pt		Au	Hg	g	TI	Pb	N.	Bi	Po	,	At	Rn
38 0.36	110	142 0.14	25 0.	52 23	240 0.58	40	0 74	430 0.48	50 0.1	0 88	420 1.47	240 0.7) 72	165 3.17	71	.9	78.5 0.46	105 0.3	5	119 0.08				
Fr	Ra	Ac		Ce	e F	r	No	I P	m	Sm	n E	u	Gd	Т	b	Dy	н	•	Er	Т	m	Yb		Lu
			L	0.	11 ().12	0.	16		0.1	13		200	D 11 0).11	21 0.	0 11 0	.16	0.1	14 ().17	120 0.3)	210 0.16
				Tł	n F	a	U	N	р	Pu	A	m	Cn	n B	k	Cf	E	5	Fn	n N	/Id	No	1	Lr
				16 0.	53 54		20 0.1	7 28 0.	.06	0.0	07													

^aMost of the θ values were supplied by N. Pearlman; references are given the A.1.P. Handbook, 3rd ed; the thermal conductivity values are from R. W. Powell and Y. S. Touloukian, Science 181, 999 (1973).

X-Ray Data Booklet--Section 1.1 ELECTRON BINDING ENERGIES

The energies are given in eV relative to the <u>vacuum level</u> for the rare gases and for H_2 , N_2 , O_2 , F_2 , and Cl_2 ; relative to the <u>Fermi level</u> for the metals; and relative to the <u>top of the valence bands</u> for semiconductors (and insulators).

	Elec	ctronic lement suratio	K 1s	L ₁ 2s	$L_2 \ 2p_{1/2}$	L ₃ 2p _{3/2}	M ₁ 3s	M ₂ 3p _{1/2}	M ₃ 3p _{3/2}	_
15		ΙH	13.6							-
15 ²	2	2 He	24.6*						Miss	inc
1s ² 2s	3	3 Li	54.7*							
1s ² 2s ²	4	Be	111.5*					\mathbf{N}	vale	nce
1s ² 2s ² 2p	ŝ	5 В	188*						D C	•
1s ² 2s ² 2p ²	2 (5 C	284.2*	va	lence l	evels		7	D.E.	3
1s ² 2s ² 2p ²	3 7	N	409.9*	37.3*	~ 9	~ 9		ornolato	$\boldsymbol{\lambda}$	
1s ² 2s ² 2p ⁴	4 8	8 0	543.1*	41.6*	~ 13	~ 13		ranalate		
1s ² 2s ² 2p ²	5 g	9 F	696.7*	~ 45	~ 17	~ 17	exi	Ιαρυίαιε	;u	
1s ² 2s ² 2p ⁶	5 10) Ne	870.2*	48.5*	21.7*	21.6*		_		
[Ne] 3s	11	Na	1070.8†	63.5†	30.65	30.81				
[Ne] 3s ²	12	2 Mg	1303.0†	88.7	49.78	49.50				
[Ne] 3s ² 3p	13	3 Al	1559.6	117.8	72.95	72.55				
[Ne] 3s ² 3p	2 14	4 Si	1839	149.7*b	99.82	99.42				
[Ne] 3s ² 3p	3 15	5 P	2145.5	189*	136*	135*		ence le	vels	
[Ne] 3s ² 3p	4 16	5 S	2472	230.9	163.6*	162.5*				
[Ne] 3s ² 3p	5 17	7 Cl	2822.4	270*	202*	200*				
[Ne] 3s ² 3p	6 18	8 Ar	3205.9*	326.3*	250.6†	248.4*	29.3*	15.9*	15.7*	
[Ar] 4	is 19	ЭК	3608.4*	378.6*	297.3*	294.6*	34.8*	18.3*	18.3*	
[Ar] 4	1s² 20) Ca	4038.5*	438.4†	349.7†	346.2*	44.3 🛊	25.4†	25.4*	
	21	l Sc	4492	498.0*	403.6*	398.7*	51.1*	28.3*	28.3*	
	22	2 Ti	4966	560.9†	460.2†	453.8†	58.7†	32.6†	32.6†	

Adding relativity to the Hamiltonian—spin-orbit coupling

$$SRUP_{1} = C_{1}^{2} m_{1}^{2} = C_{1}^{2} m_{1}^{2} = C_{1}^{2} m_{1}^{2} m_{1}$$

WITH C1 AND C2 TABULATED CLEBSCH-GORDAN OR WIGNER 3j SYMBOLS

	Some SP	IN-ORBIT S	PLITTINGS: (IN eV)
2p ⁶ -	L= 13 (AQ)	28 (Ni)	46 (7d)
201 203/2	0.4	17.8	157.0
34 10-7	L = 30 (Zn)	48 (Cd.)	64 (GL)
34 34 34	0.1	6.7	32.3
4514-3	= 74 (W)	BY (Pb)	92 (U)
45 45 8	2.2	7.0	64

INCREASE WITH Z FOR A GIVEN LEVEL. IN GENERAL:



The Photoelectric Effect, Einstein, 1905 Light can behave like a Particle!





 $hv = E_{initial} - E_{final} = E_{binding} + E_{kinetic}$

Basic Concepts and Experiments

Core-Level Photoemission

Intensities and Quantitative Analysis, the 3-Step Model Varying Surface and Bulk Sensitivity Chemical shifts Multiplet Splittings Electron Screening and Satellite Structure Magnetic and Non-Magnetic Dichroism Resonant Photoemission Photoelectron Diffraction and Holography

Valence-Level Photoemission

Band-Mapping in the Ultraviolet Photoemission Limit Densities of States in the X-Ray Photoemission Limit

Some New Directions

Photoemission with Hard X-Rays (throughout lectures) Photoemission with Standing Wave Excitation Photoemission with Spatial Resolution/Photoelectron Microscopy Temporal Resolution @ Higher Pressures

The Soft X-Ray Spectroscopies



PE = photoemission = photoelectron spectroscopy XAS = x-ray absorption spectroscopy AES = Auger electron spectroscopy XES = x-ray emission spectroscopy RIXS = resonant inelastic x-ray scattering / x-ray Raman scatt.

MATRIX ELEMENTS IN THE SOFT X-RAY SPECTROSCOPIES: DIPOLE LIMIT





Variation of Near-Edge X-Ray Absorption Fine Structure (NEXAFS) with Atomic No. for Some 3d Transition Metals

J. Stohr, "NEXAFS Spectroscopy"

Magnetic Circular Dichroism in X-Ray Absorption (XMCD)

Ferromagnetic cobalt with magnetization along incident light direction



Variation of Near-Edge X-Ray Absorption Fine Structure (NEXAFS) for Different Polymers





AES = Auger electron spectroscopy

XES = x-ray emission spectroscopy

REXS/RIXS = resonant elastic/inelastic x-ray scattering

MATRIX ELEMENTS IN THE SOFT X-RAY SPECTROSCOPIES: DIPOLE LIMIT





A very useful diagnotic observation:

Auger kinetic energies do not change with photon

Photoelectron kinetic energies shift linearly with photon energy



Figure 2. Scheme of the Auger process. A valence-level involved Auger emission is illustrated here, but the two electrons involved also could have come from core level, ϵ_4 , provided $\epsilon_5 - 2\epsilon_4 > 0$.



X-Ray Data Booklet--Section 1.1 ELECTRON BINDING ENERGIES

The energies are given in eV relative to the <u>vacuum level</u> for the rare gases and for H_2 , N_2 , O_2 , F_2 , and Cl_2 ; relative to the <u>Fermi level</u> for the metals; and relative to the <u>top of the valence bands</u> for semiconductors (and insulators).

Electronic configuration	Element	K 1s	L ₁ 2s	$L_2 2p_{1/2}$	L ₃ 2p _{3/2}	M ₁ 3s	M ₂ 3p _{1/2}	M3 3p3/2	_
1 <i>s</i>	1 H	13.6							-
1 <i>s</i> ²	2 He	24.6*						Mice	inc
1s ² 2s	3 Li	54.7*							, 5
1s ² 2s ²	4 Be	111.5*					\mathbf{N}	vale	nce
1s ² 2s ² 2p	5 B	188*						DE	~
$1s^2 2s^2 2p^2$	6 C	284.2*	Va	lence l	evels		7	D.E.	5
$1s^2 2s^2 2p^3$	7 N	409.9*	37.3*	~ 9	~ 9		ornolato	7	
$1s^2 2s^2 2p^4$	8 O	543.1*	41.6*	~ 13	~ 13		erpolate	u,	
$1s^2 2s^2 2p^5$	9 F	696.7*	~ 45	~ 17	~ 17		rapolate		
$1s^2 2s^2 2p^6$	10 Ne	870.2*	48.5*	21.7*	21.6*				
[Ne] 3s	11 Na	1070.8†	63.5†	30.65	30.81				
[Ne] 3s ²	12 Mg	1303.0†	88.7	49.78	49.50				
[Ne] 3s ² 3p	13 Al	1559.6	117.8	72.95	72.55				
[Ne] $3s^2 3p^2$	14 Si	1839	149.7*b	99.82	99.42				
[Ne] $3s^2 3p^3$	15 P	2145.5	189*	136*	135*	Val	ence le	vels	
[Ne] $3s^2 3p^4$	16 S	2472	230.9	163.6*	162.5*				
[Ne] $3s^2 3p^5$	17 Cl	2822.4	270*	202*	200*				
[Ne] $3s^2 3p^6$	18 Ar	3205.9*	326.3*	250.6†	248.4*	29.3*	15.9*	15.7*	
[Ar] 4s	19 K	3608.4*	378.6*	297.3*	294.6*	34.8*	18.3*	18.3*	
[Ar] 4s ²	20 Ca	4038.5*	438.4†	349.7†	346.2†	44.3 †	25.4*	25.4*	
-	21 Sc	4492	498.0*	403.6*	398.7*	51.1*	28.3*	28.3*	
	22 Ti	4966	560.9†	460.2*	453.8*	58.7*	32.6*	32.6*	



AES = Auger electron spectroscopy

XES = x-ray emission spectroscopy

REXS/RIXS = resonant elastic/inelastic x-ray scattering

THE AUGER PROCESS



Figure 2. Scheme of the Auger process. A valence-level involved Auger emission is illustrated here, but the two electrons involved also could have come from core level, ϵ_4 , provided $\epsilon_5 - 2\epsilon_4 > 0$.

SIMP

×

MATRIX ELEMENTS IN THE SOFT X-RAY SPECTROSCOPIES: DIPOLE LIMIT



1.3 FLUORESCENCE YIELDS FOR K AND L SHELLS

Jeffrey B. Kortright

Fluorescence yields for the K and L shells for the elements $5 \leq$ $Z \le 110$ are plotted in Fig. 1-2; the data are based on Ref. 1. These yields represent the probability of a core hole in the K or L shells being filled by a radiative process, in competition with nonradiative processes. Auger processes are the only nonradiative processes competing with fluorescence for the K shell and

110. The plotted curve for the L shell rep.

average of L_1 , L_2 , and L_3 effective yields.

Section 1.3



If fluorescence yield \equiv FY

FY = probability of radiative decay \rightarrow x-ray emission)

1 - FY = probability of non-radiative decay \rightarrow Auger electron emission



STANDARD LABORATORY X-RAY SOURCE

"Basic Concepts of XPS" Figure 2



MATRIX ELEMENTS IN THE SOFT X-RAY SPECTROSCOPIES: RESONANT EFFECTS

• X-ray emission:
$$I \propto \left| \hat{\mathbf{e}} \bullet \left\langle \varphi_f(\mathbf{1}) | \vec{\mathbf{r}} | \varphi_i(\mathbf{1}) \right\rangle \right|^2$$







1-14

Basic energetics

$$hv = E_{binding}^{Vacuum} + E_{kinetic} = E_{binding}^{Fermi} + \varphi_{spectrometer} + E_{kinetic}$$

One-Electron Picture of Photoemission from a Surface



Surface sensitivity and why we may want to go to 5-10 keV in XPS



Tanuma, Powell, Penn, Surf. and Interf. Anal. <u>43</u>, 689 (2011)
The Advanced Light Source



One of $40 \rightarrow 50$ synchrotron radiation facilities in the world





Scienta electron spectrometer (hidden)

ALS BL 9.3.1 hv = 2-5 keV



Sample prep. chamber: LEED, Knudsen cells, electromagnet,...

Scienta soft x-ray spectrometer

Permits using all relevant soft and hard x-ray spectroscopies on a single sample: PS, PD, PH; XAS (e⁻ or photon detection), XES/RIXS, with MCD, MLD



Loadlock for sample introduction

Soft x-ray spectrometer: **Scienta XES 300**

Hard X-Ray Photoemission (HXPS, HAXPES, HX-PES, HIKE...) in the World

Past workshops:

HAXPES03, ESRF--Nucl. Inst. and Meth. A, Volume 547, Issue 1, Pages 1-238 (2005) HAXPES06, SPring8-- <u>http://haxpes2006.spring8.or.jp/program.html</u> HAXPES-ALS User Meeting-- <u>http://ssg.als.lbl.gov/ssgdirectory/fedorov/workshops/index.html</u> HAXPES09-NSLS-- <u>http://www.nsls.bnl.gov/newsroom/events/workshops/2009/haxpes/</u> HAXPES11-Hasylab-- <u>http://indico.desy.de/conferenceDisplay.py?confld=3713</u>





Crucial buried functional layers & interfaces everywhere-What do we want to know: • Interface mixing/roughness/ concentration profiles • Depth-dependent magnetization profiles • Depth-dependent densities of states • Depth-dependent band structure? Some key elements in Spintronics/Semiconductors/ Sensors—multilayer nanostructures

Magnetic Random Access Memory (MRAM-Non Volatile)





Photoemission from surfaces, interfaces, bulk materials

Photoelectron



What do we want to know?

- Atomic structure, lattice distortions
- Depth profiles of composition and optical properties
- Core-levels→element specific binding energies, charge states magnetic moments, electronic configurations
- Band offsets
- Valence-band densities of states bandgaps, behavior near E_F
- Valence-band dispersions, via depth-resolved ARPES

X-ray photoemission: some key elements



Typical experimental geometry for energy- and angle-resolved photoemission measurements



Recent overview: CSF, J. Electron Spectrosc. 178–179, 2-32 (2010)

Photoemission with time-of-flight analysis



momentum component (k_x)

Measures energy and two momentum components (k_x and k_y)

ARTOF (+ Themis, LBNL,...) King, ... et al. Phys. Rev. Lett. <u>107</u>, 096802 (2011)

Photoemission with time-of-flight analysis: A topological insulator



UPPSALA

UNIVERSITET

ARToF spectroscopy: Bi₂Se₃

High resolution & High transmission

Full 3d-bandstructure in ~15 min



Basic energetics—Many e⁻ picture

$$hv = E_{binding}^{Vacuum} + E_{kinetic} = E_{binding}^{Fermi} + \varphi_{spectrometer} + E_{kinetic}$$

$$E_{binding}^{Vacuum} (Qn\ell j, K) = E_{final} (N - 1, Qn\ell j hole, K) - E_{initial} (N)$$



Typical experimental geometry for energy- and angle-resolved photoemission measurements





Basic Concepts and Experiments

Core-Level Photoemission

Intensities and Quantitative Analysis, the 3-Step Model Varying Surface and Bulk Sensitivity Chemical shifts Multiplet Splittings Electron Screening and Satellite Structure Magnetic and Non-Magnetic Dichroism Resonant Photoemission Photoelectron Diffraction and Holography

Valence-Level Photoemission

Band-Mapping in the Ultraviolet Photoemission Limit Densities of States in the X-Ray Photoemission Limit

Some New Directions

Photoemission with Hard X-Rays (throughout lectures) Photoemission with Standing Wave Excitation Photoemission with Spatial Resolution/Photoelectron Microscopy Temporal Resolution @ Higher Pressures **PHOTOELECTRON INTENSITIES—THE 3-STEP MODEL**



PHOTOELECTRON EMISSION-

BASIC MATRIX ELEMENTS + SELECTION RULES:





http://ulisse.elettra.trieste.it/servic es/elements/WebElements.html



The differential subshell photoelectric cross section—dipole limit



Higher energies: Nondipolar Angular Distributions



PHOTOELECTRON INTENSITIES—THE 3-STEP MODEL



Surface sensitivity and why we may want to go to 5-10 keV in XPS



Tanuma, Powell, Penn, Surf. and Interf. Anal. 43, 689 (2011)

Electron inelastic attenuation length in solids—the "universal curve" Photoemission is a surface sensitive experiment



Basic Concepts and Experiments

Core_TLevel Photoemission

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$$\begin{split} I(Qn\ell j) &= \\ C \int_{o}^{\infty} I_{hv}(x,y,z) \rho_{Q}(x,y,z) \frac{d\sigma_{on\ell j}(hv)}{d\Omega} \exp \left[-\frac{z}{\Lambda_{e}(E_{kin}) \sin \theta} \right] \Omega(E_{kin}, x, y) dx dy dz \\ I_{hv}(x,y,z) &= x - ray flux \\ \rho_{Q}(x,y,z) &= density of atoms Q \rightarrow quantitative analysis \\ \frac{d\sigma_{on\ell j}(hv)}{d\Omega} &= energy - dependent differential photoelectric cross section for subshell Qn\ell j \\ \Lambda_{e}(E_{kin}) &= energy - dependent inelastic attenuation length \\ \rightarrow Effective Attenuation Length (EAL) \rightarrow Mean Emission Depth (MED) \\ \Omega(E_{kin}, x, y) &= energy - dependent spectrometer acceptance solid angle \end{split}$$

C.S.F., Journal of Electron Spectroscopy and Related Phenomena 178–179 (2010) 2–32







(right). The experimental data were measured by various authors and were presented collectively by Courths and Hüfner [7.4]. The full lines showing the calculated energy bands and the density of states (*left*) are from [7.5]. The experimental data agree very well, not only among themselves, but also with the calculation

Copper projected densities of states-total and by orbital type





VALENCE-BAND PHOTOELECTRON INTENSITIES AND DENSITIES OF STATES



$$\begin{split} I(E_{kin,}Qn\ell) &= \\ C' \int_{0}^{\infty} I_{hv}(x,y,z) \rho_{Qn\ell}(E_{b},x,y,z) \frac{d\sigma_{Qn\ell}(hv)}{d\Omega} \exp \left[-\frac{z}{\Lambda_{e}(E_{kin}) \sin \theta} \right] \Omega(E_{kin},x,y) dxdydz \\ I_{hv}(x,y,z) &= x - ray flux \\ \rho_{Qn\ell}(E_{b},x,y,z) &= density of states, projected onto Qn\ell character \\ \frac{d\sigma_{Qn\ell}(hv)}{d\Omega} &= energy - dependent differential photoelectric cross section for subshell Qn\ell \\ \Lambda_{e}(E_{kin}) &= energy - dependent inelastic attenuation length \\ \rightarrow Mean Emission Depth \\ \Omega(E_{kin},x,y) &= energy - dependent spectrometer acceptance solid angle \end{split}$$

PHOTOELECTRON INTENSITIES—THE 3-STEP MODEL



One-Electron Picture of Photoemission from a Surface



Electron Refraction at the Surface Due to the Inner Potential



Electron Refraction at the Surface Due to the Inner Potential



C. S. F., Prog. Surf. Sci. 1984, 16, 275
PHOTOELECTRON INTENSITIES—THE 3-STEP MODEL



 $exp(-\mu_{x}L_{x}) = exp(-L_{x}/\Lambda_{x})$ $n = 1 - \delta - i\beta$ (Kramers-Kronig) $\approx 1 - (r_{0}\lambda_{x}^{2}/2\pi)\Sigma_{i}n_{i}f_{xi}(0)$ $\mu_{x} = 4\pi\beta/\lambda_{x}$ Multi-atom

Some basic measurements:

Wave, LP, RCP, LCP

Standing

 λ_{SW}

Electrons out

$$\theta_{X}^{R} = \theta_{X}^{I}$$

 $\lambda_{\text{SW}} = \lambda_{\text{X}} / (2 \sin \theta_{\text{X}}^{\text{I}})$ $\theta_{\text{CRIT}}^{\text{I}} = (2\delta)^{1/2}$

X-lay Flourescence Holography (XFH, XFH⁻¹), Resonant XFH (RXFH)

 $exp(-L_e/\Lambda_e)$

XES, RIXS

XFH⁻¹, RXFH

n

θ

XFH

hv'

R⊀ REXS, XRD

XAS, XRO

PS, PD, PH

CD, MCD, SP

 X-ray Emission Spectroscopy (XES), Resonant Inelastic X-ray Scattering (RIXS)
 Resonant Elastic X-ray Scattering (REXS)
 X-Ray Diffraction (XRD)
 X-ray Absorption Spectroscopy (XAS)
 X-Ray Optical measurements (XRO)
 Photoelectron Spectroscopy (PS), Diffraction (PD), Holography (PH)
 + Circular Dichroism (CD), Magnetic CD (MCD), Spin Polarization (SP)





Online data and calculations at:

http://www-cxro.lbl.gov/optical_constants/

(E.G. See pp. 1-38, 1-44, 5-18-5-19 in X-Ray Data Booklet)

Index of refraction = $n = 1 - \delta - i\beta$

 δ = + no. = refractive decrement << 1 (Sometimes negative through absorption resonances)

 β = + no. = absorptive decrement << 1

 δ and β linked by Kramers-Kronig transform

n also = 1 – $(r_e/2\pi)\lambda_{hv}^2 \sum n_i f_i$ (0=fwd. scatt.)

 r_{e} = classical electron radius $= e^{2/4} \pi \epsilon_0 m_e^2 = 2.817 \times 10^{-15} m_e^2$ $\lambda_{hv} = x$ -ray wavelength

 $n_i = no. i$ atoms per unit volume

 f_1 = x-ray scattering factor for ith type of atom, in forward direction

Exponential absorption length = $I_{abs} = \lambda_{hv}/(4\pi\beta) = \Lambda_{hv}$

 θ_{CRIT} = critical grazing angle at which reflectivity begins ($R \approx 0.20$) = [28]^{0.5}

Au Density=19.32 delta (dash) beta (solid 0 Beta 0.01Delta, -33 10 0^{-4}

200

Photon Energy (eV)

500

1000

2000

100

50

Atomic Scattering Factors

http://www-cxro.lbl.gov/optical_constants/



Other x-ray web resources.

These pages utilize JavaScript, but the decaffeinated versions are still available.

Reference

B.L. Henke, E.M. Gullikson, and J.C. Davis. *X-ray interactions: photoabsorption, scattering, transmission, and reflection at E 50-30000 eV, Z 1-92*, Atomic Data and Nuclear Data Tables Vol. **54** (no.2), 181-342 (July 1993).

CXRO ALS

By Eric Gullikson. Please direct any comments to <u>EMGullikson@lbl.gov</u> Server Statistics © 1995-2001

ENHANCED SURFACE SENSITIVITY @ GRAZING

SOME X-RAY OPTICAL EFFECTS: REDUCED PENETRATION DEPTHS AND INCREASED REFLECITIVITY AT GRAZING INCIDENCE ANGLES

 $\label{eq:GRIT} \begin{array}{l} \textbf{θ_{CRIT} = Grazing angle at which} \\ \textbf{reflectivity begins} \\ \textbf{(R} \approx \textbf{0.20)} \end{array}$

= [2δ]^{0.5}



Optical constants through Mn 2p edges of MnO— Web data <u>without absorption peaks</u>





Basic Concepts and Experiments

Core-Level Photoemission



Valence-Level Photoemission

Band-Mapping in the Ultraviolet Photoemission Limit Densities of States in the X-Ray Photoemission Limit

Some New Directions

Photoemission with Hard X-Rays (throughout lectures) Photoemission with Standing Wave Excitation Photoemission with Spatial Resolution/Photoelectron Microscopy Temporal Resolution @ Higher Pressures

Chemical shifts: Looking into the silicon dioxide layer with photoelectron spectroscopy



Shift
$$\approx q_{si} K_{si2p,si3p} =$$

 $q_{si} \int \varphi_{2p}^{*}(\vec{r}_{1}) \varphi_{3p}^{*}(\vec{r}_{2}) \frac{e^{2}}{r_{12}} \varphi_{2p}(\vec{r}_{1}) \varphi_{3p}(\vec{r}_{2}) dV_{1} dV_{2}$

Himpsel et al., Phys. Rev. B 38, 6086 ('88)



Enhancing surface sensitivity at grazing exit angles





CSF, Prog. in Surf. Sci. <u>16</u>, 275 (1984)



Core and valence photoemission



N. Mannella et al., Phys. Rev. Lett. <u>92</u>, 166401 (2004)

Temperature dependence of Mn3s and O1s spectra: La_{0.7}Sr_{0.3}MnO₃



N. Mannella et al., Phys. Rev. Lett. <u>92</u>, 166401 (2004)

Core and valence photoemission



N. Mannella et al., Phys. Rev. Lett. <u>92</u>, 166401 (2004)

Basic Concepts and Experiments

Core-Level Photoemission

Intensities and Quantitative Analysis, the 3-Step Model Varying Surface and Bulk Sensitivity

Chemical shifts

Multiplet Splittings

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Multiplet splitting in core levels of transition metal oxides



INTENSITIES IN PHOTOBLECTRON SPECTRA!



PLUS DIFFRACTION EFFECTS IN 4 ESCAPE

ORIGIN OF MULTIPLET SPLITTINGS IN Mn²⁺: "ONE-ELECTRON" THEORY



ORIGIN OF MULTIPLET SPLITTINGS IN Mn²⁺: "ONE-ELECTRON" THEORY



CORE-LEVEL MULTIPLET SPLITTINGS IN Mn COMPOUNDS



"Basic Concepts of XPS" Figure 31





Temperature dependence of Mn3s and O1s spectra: La_{0.7}Sr_{0.3}MnO₃



N. Mannella et al., Phys. Rev. Lett. <u>92</u>, 166401 (2004)



N. Mannella et al., PRL <u>92</u>, 166401 ('04); PRB <u>70</u>, 224433 ('04), and to be publ.

Basic Concepts and Experiments

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Basic energetics—Many e⁻ & many atom picture



INTENSITIES IN PHOTOBLECTRON SPECTRA!



PLUS DIFFRACTION EFFECTS IN 4 ESCAPE



 $\Psi_{\text{final},K}(N-1) = C_{1,K}\Phi_1(2p_{1/2}^22p_{3/2}^33d^{10} + C\ell \text{ hole}) + C_{2,K}\Phi_2(2p_{1/2}^22p_{3/2}^33d^9)$

Van der Laan et al., Phys. Rev. B 23 (1981) 4369

Many-electron and screening effects: $La_{0.7}Sr_{0.3}MnO_3$, hv = 7700 eV



Basic Concepts and Experiments

Core-Level Photoemission

Intensities and Quantitative Analysis, the 3-Step Model Varying Surface and Bulk Sensitivity

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Typical experimental geometry for energy- and angle-resolved photoemission measurements



st Expt. Magnetic Circular Dichroism 1-e⁻ Theo





Menchero, Phys. Rev. B 57 (1998)993



Van der Laan et al., J. Phys. Condens. Matter 12 (2000) L275

Magnetic circular dichroism with soft and hard x-rays



CSF, J. Electron Spectrosc. <u>178–179, 2-32</u> (2010)

700

Basic Concepts and Experiments

Core-Level Photoemission

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Adding relativity to the Hamiltonian—spin-orbit coupling

$$SRUP_{1} = C_{1}^{2} m_{1}^{2} = C_{1}^{2} m_{1}^{2} = C_{1}^{2} m_{1}^{2} m_{1}$$

WITH C1 AND C2 TABULATED CLEBSCH-GORDAN OR WIGNER 3j SYMBOLS

Photoelectron spin polarization from spin-orbit coupling and circularly-polarized radiation—The Fano Effect



Photoelectron spin polarization from spin-orbit coupling and circularly-polarized radiation—The Fano Effect



Fano effect and Spin polarization in core photoelect



Basic Concepts and Experiments

Core-Level Photoemission

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Resonant Photoemission—Mn 3d



Resonant Photoemission—Mn 3d

Ex. - Mn atom: Mn3d emission, resonance with Mn3p -Photo e^- , $E \approx 50 \text{ eV}$ <Ef lê•r l Mn3d> $\ell = p + f$ <Ef, Mn3p 🚰 Mn3d, Mn3d> $hv_{3p} \approx 50 \text{ eV}$ Mn3d Strong <Mn3d lê•rl Mn3p> Mn3p On Expt. (Krause et al.) Atomic 7.0 **重 3d** Mn(g) 6.0 Theory (Garvin et al.) - MBPT 5.0 --- HF I_{Mn3d} 4.0 Resonant (\pm) ≈ 0.63 3.0 hv_{3p} Off 2.0 Non-Resonant $\equiv 1.0$ 1.0 0 30 90 100 100 20 40 50 60 70 80 Photon Energy, hv (eV)

MATRIX ELEMENTS IN THE SOFT X-RAY SPECTROSCOPIES: RESONANT EFFECTS

• <u>Resonant photoemission:</u>

$$I \propto \left| \langle \varphi_{f}(1) | \hat{e} \bullet \vec{r} | \phi_{i}(1) \rangle + \sum_{m} \langle \varphi_{f}(1) \varphi_{1}(2) | \frac{e^{2}}{r_{12}} | \varphi_{i}(1) \varphi_{m}(2) \rangle \langle \varphi_{m}(1) | \hat{e} \bullet \vec{r} | \varphi_{1}(1) \rangle \right|^{2} \\ \times \delta(h_{V} - (E_{m} - E_{1}))$$
Direct
$$Vacuum - \frac{\varphi_{f}}{\varphi_{0}} - \overline{Resonant}$$

$$W = \frac{P_{0}}{\varphi_{1}}$$

$$I \propto \sum_{f} \left| \sum_{m} \frac{\langle \Psi_{f}(N) | \hat{e} \bullet \vec{r} | \Psi_{m}(N) \rangle \langle \Psi_{m}(N) | \hat{e} \bullet \vec{r} | \Psi_{i}(N) \rangle}{h\nu + E_{i}(N) - E_{m}(N) - i\Gamma} \right|^{2} \frac{h\nu}{\sqrt{\frac{4}{\Delta E} \Psi_{f}}} h\nu - \Delta E$$
$$\times \delta(h\nu - (E_{m}(N) - E_{i}(N)))$$

Resonant Photoemission—La_{0.6}Sr_{0.4}MnO₃, Mn 3d with Mn 2p



K. Horiba et al. | Journal of Magnetism and Magnetic Materials 272–276 (2004) 436–437

Basic Concepts and Experiments

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Typical experimental geometry for energy- and angle-resolved photoemission measurements



PHOTOELECTRON INTENSITIES—THE 3-STEP MODEL





Photoelectron Diffraction: Single Scattering Theory



ENERGY DEPENDENCE OF ELECTRON ELASTIC SCATTERING



Sagurton et al. Surf. Sci. 182, 287 ('84)



Energy dependence of photoelectron diffraction: Theory



Much more forward peaked at higher energy, weaker in directions away from forward

Photoelectron Diffraction with soft and hard x-ray excitation: two viewpoints

The scattering of photoelectrons from localized sources can be described in real space (multiple scattering cluster) and reciprocal space (dynamical theory of electron diffraction)



A. Winkelmann et al, New J. Phys <u>10</u> (2008) 113002

Photoelectron Diffraction with soft and hard x-ray excitation: two viewpoints, expt. vs. theory



A. Winkelmann et al, New J. Phys <u>10</u> (2008) 113002

Bulk sensitive HXPD of Si 1s



Kobata et al., SPring8: Surf. Interf. Anal., http://onlinelibrary.wiley.com/doi/10.1002/sia.3760/pdf

Hard x-ray photoelectron diffraction--Theory: Sensitivity to lattice distortions and atomic site type?

Si(111)-6 keV: Impurity atom on lattice site (Si) vs. tetrahedral interstitial (T)





A. Winkelman, J. Garcia de Abajo, MPI Halle, CF, New Journal of Physics <u>10</u> (2008) 113002

Missing Kikuchi bands-->"forbidden reflections"

Basic Concepts and Experiments

Core-Level Photoemission

Intensities and Quantitative Analysis, the 3-Step Model Varying Surface and Bulk Sensitivity Chemical shifts Multiplet Splittings Electron Screening and Satellite Structure Magnetic and Non-Magnetic Dichroism Resonant Photoemission Photoelectron Diffraction and Holography

Valence-Level Photoemission

Band-Mapping in the Ultraviolet Photoemission Limit Densities of States in the X-Ray Photoemission Limit

Some New Directions

Photoemission with Hard X-Rays (throughout lectures) Photoemission with Standing Wave Excitation Photoemission with Spatial Resolution/Photoelectron Microscopy Temporal Resolution @ Higher Pressures

Diffraction and Holography: What's the Difference?



Photoelectron Holography: An Additional Trick

Holography: $I_{o}(k)$ **Reference and** scattered interfere \rightarrow phase relation point atom preserved source Use an "inside-source": atomic or nuclear emitter (Szöke, in "Short Wavelength **Radiation: Generation and** Applications", D. Attwood and J. Bokor, Eds., $\boldsymbol{\chi}(\vec{\boldsymbol{k}}) = [\boldsymbol{I}(\vec{\boldsymbol{k}}) - \boldsymbol{I}_o(\vec{\boldsymbol{k}})] / \boldsymbol{I}_o(\vec{\boldsymbol{k}})$ **AIP Conference Proceedings** No. 147 (1986)) Ho log raphic image of scatterers =

$$U(\vec{r}) = \left| \iiint \chi(\vec{k}) \exp[i\vec{k} \bullet \vec{r} - ikr] d^{3}k \right|$$

Differential photoelectron holography in Cu(001) —Cu 3p emission



Omori et al., Phys. Rev. Lett. 88 (2002) 5504

Derivative photoelectron holography: As and Si emission from As/Si(111):

$$U(\vec{r}) = \left| \iiint \chi(\vec{k}) \exp[i\vec{k} \cdot \vec{r} - ikr] d^{3}k \right|$$

with $\chi = \frac{I(\vec{k}) - I_{o}}{I_{o}}$
and $I(\vec{k})$ from int egration of log arithmic derivative

$$L(hv, \hat{k}) = \frac{I(hv + \delta, \hat{k}) - I(hv - \delta, \hat{k})}{\left[I(hv + \delta, \hat{k}) + I(hv - \delta, \hat{k})\right]\delta}$$
$$I(\vec{k}) \equiv I(k, \hat{k}) = A \int L(hv, \hat{k}) d^{3}k$$

Luh et al. Phys. Rev. Lett., <u>81</u>, 4160 (1998)



Emitter (As)









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Resonant Photoemission
Photoelectron Diffraction and Holography

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Typical experimental geometry for energy- and angle-resolved photoemission measurements



PHOTOELECTRON EMISSION-

BASIC MATRIX ELEMENTS + SELECTION RULES:



BRILLOUIN ZONE

> "Basic Concepts of XPS" Chapter 3

DIRECT TRANSITIONS

BUT LATTICE VIBRATIONS => SUM OVER KPHONON => FRACTION DIRECT : DEBNE- WALLER FACTOR

= exp[-92 42]

Valence-band photoemission: Angle-Resolved Photoemission (ARPES)





Typical experimental geometry for energy- and angle-resolved photoemission measurements





Huebner, Phys. Rev. B 42, 11553 (1990)

Angle-Resolved Photoemission from ferromagnetic Ni(111) hv = 21.2 eV Spin-split bands



Kreutz et al., Phys. Rev. B 58 (1998) 1300

Basic Concepts and Experiments

Core-Level Photoemission

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ARPES—How high can we go in energy and temperature?



Fraction DTs \approx Debye-Waller factor = $W(T) \approx exp[-(k^f)^2 < u^2(T) >]$ $\approx exp[-C_1(k^f)^2T/(m\Theta_D^2)] \approx exp(-C_2E_{kin}T)$

ARPES → bands, quasiparticles (Low hv, Low T, High angul. Res.)

Shevchik, Phys. Rev. B 16, 3428 (1977) Hussain....CF, Phys. Rev. B 34 (1986) 5226 XPS→DOS (High h_V, High T, Low angul. Res.)

VALENCE-BAND PHOTOELECTRON INTENSITIES AND DENSITIES OF STATES



$$\begin{split} I(E_{kin,}Qn\ell) &= \\ C' \int_{0}^{\infty} I_{hv}(x,y,z) \rho_{Qn\ell}(E_{b},x,y,z) \frac{d\sigma_{Qn\ell}(hv)}{d\Omega} \exp \left[-\frac{z}{\Lambda_{e}(E_{kin}) \sin \theta} \right] \Omega(E_{kin},x,y) dxdydz \\ I_{hv}(x,y,z) &= x - ray flux \\ \rho_{Qn\ell}(E_{b},x,y,z) &= density of states, projected onto Qn\ell character \\ \frac{d\sigma_{Qn\ell}(hv)}{d\Omega} &= energy - dependent differential photoelectric cross section for subshell Qn\ell \\ \Lambda_{e}(E_{kin}) &= energy - dependent inelastic attenuation length \\ \rightarrow Mean Emission Depth \\ \Omega(E_{kin},x,y) &= energy - dependent spectrometer acceptance solid angle \end{split}$$

Gold Valence Spectrum



In the XPS Limit— Comparison to theoretical DOSs



Au subshell photoelectric cross section ratios: Au6s/Au5d = 0.012 at 1.5 keV and 0.028 at 6 keV→6s more imp. at 6 keV x 2.5x



Phonon effects: Approximate fraction of "good" direct transitions \approx Debye-Waller factor = $W(T) \approx exp[-g^2 < u^2(T) >]$ = Mean-squared vibrational displacement

The Photoelectric Effect, Einstein, 1905 Light can behave like a Particle!





(E_{kinetic}-E_{recoil})

,direction,spin

 $hv = E_{initial} - E_{final} = E_{binding} + (E_{kinetic} - E_{recoil})$

Angle-Resolved Photoemission at High Energy--How high can we go?:



Angle-Resolved Photoemission (ARPES) with soft x-rays: W(110) at 860 eV



Experiment and theory: W(110)--860 eV



LMU

Ludwig

Maximilians-Universität

The Debye-Waller Factor

Estimate of the Fraction of Direct Transitions and Max. Recoil Effect



L. Plucinski, et al. PRB <u>78</u>, 035108 (2008)

ARPES with a <u>non-monochromatized lab. x-ray source</u>: $h_V = 1253.6 \text{ eV}$, T = ~77K, W = 0.82









theta





Plucinski

Hard x-ray ARPES from GaAs(001)-3.2 keV, 30 K, W = 0.31



Theory- Pickett, Ylvisaker

Hard x-ray ARPES for GaAs(001): 3.2 keV



(E_f) 0 a

2

[001]

Detector Angle (°)

DOS

Gray, Minar et al., Nature Materials 10, 759 (2011)

Hard x-ray ARPES--GaAs and the dilute magnetic semiconductor Ga_{0.97}Mn_{0.03}As

How does Mn alter the electronic structure so as to produce ferromagnetic coupling? Two differing views:



GaAs doped with Mn: a magnetic semiconductor Ga_{0.96}Mn_{0.04}As--HXPS: T = 20K, Broad Survey



Samples: Stone, Dubon Expt.-Gray, Papp, Ueda, Yamashita, Kobayashi Theory- Pickett, Ylvisaker, Minar, Braun, Ebert

Hard x-ray ARPES--GaAs and DMS Ga_{0.97}Mn_{0.03}As Comparing Experiment and One-Step KKR Theory



Hard x-ray ARPES--GaAs and the dilute magnetic semiconductor Ga_{0.97}Mn_{0.03}As

How does Mn alter the electronic structure so as to produce ferromagnetic coupling? Two differing views:





Basic Concepts and Experiments

Core-Level Photoemission

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Typical experimental geometry for energy- and angle-resolved photoemission measurements



Surface sensitivity and why we may want to go to 5-10 keV in XPS



Tanuma, Powell, Penn, Surf. and Interf. Anal. 43, 689 (2011)



Kover, Werner, Drube, et al., Surf. & Int. Anal. 38, 569 (2006)

Looking into nanoscale devices--Variable takeoff-angle Si 1s photoelectron spectra from NiGe(12-nm)/SiO₂(12-nm)/Si(100)



Hattori et al., Int. J. High Speed Electronics 16 (2006) 353

Hard x-ray photoemission--Quantitative analysis of peak intensities using theoretical cross sections: $La_{0.7}Sr_{0.3}MnO_3$, hv = 7700 eV



Quantitative analysis of peak intensities using theoretical cross sections (Scofield): $La_{0.7}Sr_{0.3}MnO_3$, hv = 7700 eV



Electronic Structure of Strained Manganite Thin Films with Room Temperature Ferromagnetism Investigated by Hard X-ray Photoemission Spectroscopy: La_{0.85}Ba_{0.15}MnO₃



Temperature dependence of Mn2p spectra: La_{0.7}Sr_{0.3}MnO₃ New satellite structures in core spectra



 \rightarrow Suggests bulk electronic structure not reached until ca. 8 nm depth

Offi, Mannella, et al., Phys. Rev. B 2008, 77, 174422

Basic Concepts and Experiments

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Some New Directions

Photoemission with: Hard X-Rays (throughout lectures)

Standing Wave Excitation Spatial Resolution/Photoelectron

Spatial Resolution/Photoelectron Microscopy Temporal Resolution

@ Higher Pressures

Typical experimental geometry for energy- and angle-resolved photoemission measurements



PHOTOELECTRON INTENSITIES—THE 3-STEP MODEL





Standing wave formation in reflection from a surface, or single-crystal Bragg planes⁺, or a multilayer mirror

Incident

Reflected



*Standing waves via Bragg reflection of hard x-rays: Batterman, Phys. Rev A 133, 759 (1964)

Standing Wave Behavior During a Rocking Curve Scan



+Same general forms if photon energy is scanned

With thanks to Martin Tolkiehn, Dimitri Novikov, DESY

Site-specific valence electronic structure of SrTiO3


Case study: Standing wave/rocking curve analysis of an epitaxial SrTiO₃/La_{0.67}Sr_{0.33}MnO₃ interface: Resonant soft x-ray excitation



Standing wave/rocking curve analysis of an epitaxial SrTiO₃/La_{0.67}Sr_{0.33}MnO₃ interface: hard x-ray excitation



Gray et al., Phys. Rev. B 82, 205116 (2011) Samples: Ramesh, Huijben







Fitting of Rocking Curves—All Elements Present, Soft and Hard X-rays



Gray et al., Phys. Rev. B 82, 205116 (2011)

STO/LSMO-Resonant soft x-ray standing wave/rocking curves at 833 eV: core photoelectron peaks compared to calculated standing-wave field



state shift at interface
seen in Mn 3p
≻No change in Mn 3s
≻No change in Ti 3p—
near surface



Gray, Yang et al., Phys. Rev. B 82, 205116 (2011)



STO/LSMO-Explaining the Difference Between Mn 3p and Mn 3s behavior



X-ray photoemission: some key elements



ARPES—How high can we go in energy and temperature?



Fraction DTs \approx Debye-Waller factor = $W(T) \approx exp[-(k^f)^2 < u^2(T) >]$ $\approx exp[-C_1(k^f)^2T/(m\Theta_D^2)] \approx exp(-C_2E_{kin}T)$

ARPES → bands, quasiparticles (Low hv, Low T, High angul. Res.)

Shevchik, Phys. Rev. B 16, 3428 (1977) Hussain....CF, Phys. Rev. B 34 (1986) 5226 XPS→DOS (High h_V, High T, Low angul. Res.)

SrTiO₃ and La_{0.67}Sr_{0.33}MnO₃ band structures and DOS



STO/LSMO-Standing wave/rocking curves of valence region: 833 eV, 300K Debye-Waller ≈ 0.013→ DOS limit



The Advanced Light Source

Prior resonant PS: Fujimori et al., J.A.P 99, 08S903 (2006)

Standing-wave angle-resolved photoemission



STO/LSMO Depth-resolved ARPES: hv=833 eV, 20K

Room-Temperature DOS Spectrum:

 k_{x}

k,



k_x

 k_{x}

 k_{x}

First comparison to one-step photoemission theory for LSMO



Theory from: H. Ebert, J. Minar et al., Munich: one-step timereversed LEED, with matrix elements

A. Gray, J. Minar et al., TBP

First comparison to one-step photoemission theory for STO/LSMO



Standing wave formation in reflection from a surface, or single-crystal Bragg planes⁺, or a multilayer mirror

Incident

Reflected



1. <u>Rocking curve</u>:

 $I(\theta_{inc}) \propto 1 + R(\theta_{inc}) + 2\sqrt{R(\theta_{inc})} f \cos[\varphi(\theta_{inc}) - 2\pi P]$

2. Photon energy scan:

 $I(hv) \propto 1 + R(hv) + 2\sqrt{R(hv)} f \cos[\varphi(hv) - 2\pi P]$

with: f = coherent fraction of atoms, P = phase of coherent-atom position

<u>3. Phase scan with wedge-shaped sample ("Swedge" method):</u>

Fe/Cr GMR—Yang, J. Phys. Cond. Matt. <u>14</u>, L406 (2002); ; Co/CoFeB/Al₂O₃ TMR—Yang, J. Phys.: Cond. Matt. <u>18</u>, L259 (2006); Fe/MgO TMR— Döring, Yang, Balke—PRB B <u>83</u>, 165444 (2011) & <u>84</u>, 184410 (2011)







Soft x-ray standing-wave wedge scans through a magnetic tunnel junction



Balke, Yang et al., Phys. Rev. B 84, 184410 (2011)



Yang, Balke et al., Phys. Rev. B <u>84</u>, 184410 (2011)



Balke, Yang et al., Phys. Rev. B <u>84</u>, 184410 (2011)

Final profiles of concentration and magnetization





Yang, Balke et al., Phys. Rev. B <u>84</u>, 184410 (2011)

MgO/Fe tunnel junctionthe real interface



Meyerheim PRL 87, 076102 (2001).

Is there FeO at the interface?
What is the density of states at the interface?
Δ₁ controls tunneling?
Can we see bands at epitaxial interfaces?
(Future project)



Mertig et al., PRB <u>73</u>, 214441 (2006)



Butler et al., PRB 63, 054416 (2001)

Standing wave/wedge derivation of depth-dependent densities of states: Fe/MgO tunnel junction

 $\tilde{D}_{L}(E_{kin,j})$ = matrix-element weighted density of states in layer L



Yang, Balke et al., Phys. Rev. B <u>84</u>, 184410 (2011)

Standing wave/wedge derivation of depth-dependent densities of states: Fe/MgO tunnel junction



Yang, Balke et al., Phys. Rev. B <u>84</u>, 184410 (2011)



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Some New Directions

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@ Higher Pressures

Kiskinova Locatelli

Typical experimental geometry for energy- and angle-resolved photoemission measurements





Basic Concepts and Experiments

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Some New Directions

Phote Phote Phote

Photoemission with Hard X-Rays (throughout lectures) Photoemission with Standing Wave Excitation Photoemission with Spatial Resolution/Photoelectron Microscopy Temporal Resolution

@ Higher Pressures

Adding depth resolution to the photoelectron microscope via standing wave excitation



Standing wave effects in a photoelectron microscope











F. Kronast, H. Dürr, BESSY D. Buergler, R. Scheiber,C. Schneider, Jülich Yang, IBM, CF, Appl. Phys. Lett. 93, 243116 (2008)

Third type: Imaging Zone-Plate X-ray microscope XM-1 @ ALS




Rotenberg, Bostwick, ALS-LBNL

Basic Concepts and Experiments

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@ Higher Pressures

Surface sensitivity and why we may want to go to 5-10 keV in XPS



Tanuma, Powell, Penn, Surf. and Interf. Anal. <u>43</u>, 689 (2011)

Challenges for high-pressure photoemission: analyzer Pressure and short electron mean free fath



լուու

IMFP: N₂ @ 500 eV ~ 0.003 mm = 3 microns 1 atm 20 torr ~ 0.1 mm = 100 microns $1 \text{ torr} \sim 2 \text{ mm}$



Smaller x-ray spot & $z \rightarrow$ Higher Pressure...

Detector

The first endstation at a SR facility (ALS, BL9.3.2):

D.F. Ogletree, H. Bluhm, G. Lebedev, C.S. Fadley, Z. Hussain, M. Salmeron, Rev. Sci. Instrum. 73 (2002) 3872.

A good review paper:

M. Salmeron and R. Schlögl, Surf. Sci. Rep. 63, 169-199 (2008).

Bridging the Pressure Gap: Chemical-State- and Time- Resolved Oxidation of Si at Multi-Torr Pressures



Watching the oxide grow in real time: constant P, variable T



Time-resolved core-level XPS(→HXPS) as a monitor of a charge density wave in Mott insulator 1T-TaS₂



Hellman et al., PRL 105, 187401 (2010)

Typical experimental geometry for energy- and angle-resolved photoemission measurements



Basic Concepts and Experiments

The photoelectric effect: 100+ years old! Much enhanced by synchrotron radiation, now moving to the harder x-ray regime and short-pulse FELs

Core-Level Photoemission— an element specific probe

Intensities and the Three-Step Model— quantitative near-surface analysis Varying Surface and Bulk Sensitivity— vary energy or takeoff angle standing waves

Chemical shifts— chemical state specific spectroscopy and stoichiometry Multiplet Splittings— spin state, valence configuration(s) Electron Screening and Satellite Structure— valence configuration(s) Magnetic Circular Dichroism– long-range magnetic order Resonant photoemisson– enhancing a given atom's contribution Photoelectron Diffraction and Holography– element-specific atomic structure

Valence-Level Photoemission

Band-Mapping in the Ultraviolet Photoemission Limit– valence electronic states Fermi surfaces, for many materials and nanostructures,

Densities of States in the X-Ray Photoemission Limit– densities of states with greater bulk sensitivity, low temp. measurements→ band mapping

Some New Directions

Photoemission with Hard X-Rays– deeper probing of nanostructures,

densities of states, true bulk electronic structure

Photoemission with Standing Wave (SW) Excitation- selective probing of buried interfaces and layers

Photoemission with: Spatial Resolution- nanoscale band mapping and

(several spectromicroscopies)

Temporal Resolution–lasers, FELs

@ Higher Pressures- several torr, Realtime kinetics

Miniussi et al., Ru T dependent lineshapes